

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Wang

Application No.: 10/723,746

Filed: 11/25/2003

Title: POLISHING COMPOSITION FOR CMP  
HAVING ABRASIVE PARTICLES

Attorney Docket No.: 03049US

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Art Unit:  
1765Examiner:  
L. Umez EroniniRECEIVED  
CENTRAL FAX CENTER  
MAR 22 2006RESPONSE

Dear Sir:

In response to the Office Action of December 22, 2005, having a shortened statutory  
deadline of March 22, 2006, please amend this application as follows:

~~Do Not Enter~~  
~~Amendment~~  
~~L. J. M-E~~  
~~3/25/2006~~

Entered  
w/ RCE  
4/17/06  
wm.